**Section 307.3126 Secondary Tantalum**

a) Applicability. This Section applies to discharges resulting from the production of tantalum at secondary tantalum facilities.

b) Specialized Definitions. The Board incorporates by reference 40 CFR 421.281 (2003). This incorporation includes no later amendments or editions.

c) Existing Sources. These sources must comply with the general and specific pretreatment requirements of Subpart B.

d) New Sources

1) The Board incorporates by reference 40 CFR 421.286 (2003). This incorporation includes no later amendments or editions.

2) No person subject to the pretreatment standards incorporated by reference in subsection (d)(1) may cause, threaten, or allow the discharge of any contaminant to a POTW in violation of those standards.

3) "New source" means any building, structure, facility, or installation whose construction commenced after June 27, 1984.

(Source: Amended at 47 Ill. Reg. 4662, effective March 23, 2023)